## Anil G Khairnar

## List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/12068154/publications.pdf

Version: 2024-02-01

1684188 1872680 7 148 5 6 citations h-index g-index papers 8 8 8 160 docs citations times ranked citing authors all docs

#	Article	IF	CITATIONS
1	Structural and electrical characteristics of RF-sputtered HfO2 high-k based MOS capacitors. Solid-State Electronics, 2011, 62, 44-47.	1.4	73
2	Sol–gel deposited ceria thin films as gate dielectric for CMOS technology. Bulletin of Materials Science, 2013, 36, 259-263.	1.7	30
3	HfO2 gate dielectric on Ge $(1\ 1\ 1)$ with ultrathin nitride interfacial layer formed by rapid thermal NH3 treatment. Applied Surface Science, 2016, 364, 747-751.	6.1	18
4	High Dielectric Constant ZrO2 Films by Atomic Layer Deposition Technique on Germanium Substrates. Silicon, 2016, 8, 345-350.	3.3	14
5	Preparation of rare earth CeO2 thin films using metal organic decomposition method for metal-oxide–semiconductor capacitors. Journal of Materials Science: Materials in Electronics, 2017, 28, 12503-12508.	2.2	11
6	Investigation of Current Conduction Mechanism in HfO2 Thin Film on Silicon Substrate. Environmental Science and Engineering, 2014, , 25-27.	0.2	2
7	Capacitance-Voltage Measurement of SiO2/GeOxNy Gate Stack on Surface Passivated Germanium. Environmental Science and Engineering, 2014, , 9-11.	0.2	0